



UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Address: COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/824,422	04/15/2004	Yutaka Tanaka	00862.022285.1	6472
5514	7590	04/04/2006	EXAMINER	
FITZPATRICK CELLA HARPER & SCINTO 30 ROCKEFELLER PLAZA NEW YORK, NY 10112			MOORE, KARLA A	
			ART UNIT	PAPER NUMBER
			1763	

DATE MAILED: 04/04/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

Cm

Office Action Summary	Application No.	Applicant(s)	
	10/824,422	TANAKA ET AL.	
	Examiner	Art Unit	
	Karla Moore	1763	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) Responsive to communication(s) filed on 18 January 2006.
 2a) This action is FINAL. 2b) This action is non-final.
 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) Claim(s) 23-27 is/are pending in the application.
 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
 5) Claim(s) _____ is/are allowed.
 6) Claim(s) 23-27 is/are rejected.
 7) Claim(s) _____ is/are objected to.
 8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) The specification is objected to by the Examiner.
 10) The drawing(s) filed on 15 April 2004 is/are: a) accepted or b) objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. 29/897,930.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- 1) Notice of References Cited (PTO-892)
 2) Notice of Draftsperson's Patent Drawing Review (PTO-948)
 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
 Paper No(s)/Mail Date _____
- 4) Interview Summary (PTO-413)
 Paper No(s)/Mail Date. _____
- 5) Notice of Informal Patent Application (PTO-152)
 6) Other: _____

DETAILED ACTION***Claim Rejections - 35 USC § 103***

1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

2. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

3. Claims 23-27 are rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent No. 6,224,679 to Sasaki et al. in view of U.S. Patent No. 5,413,664 to Yagi et al.

4. Sasaki et al. disclose a semiconductor processing apparatus comprising a plurality of processing chambers/units substantially as claimed and comprising: a process chamber (not illustrated, column 4, rows 63 through column 5, row 1 and column 5, rows 51-56); a load lock chamber including first (15A) and second gate valves (19), and connected to the process chamber (13) through a conveyance chamber via said gate valve (15A); a booth (14) connected to said load lock chamber via said second gate valve; a transfer mechanism (13A) arranged in said booth (during transfer) and configured to transfer the wafer from another apparatus different

from said exposure apparatus into said load lock chamber through said booth; and a gas flow forming mechanism (multiple part numbers, 20-28 and 31-32) including a filter (21 and 22) and configured to cause gas from said filter to flow through said booth.

5. However, Sasaki et al. fail to teach said processing apparatus specifically comprising a process chamber capable of exposing a wafer to light via a mask.

6. Yagi et al. teach that the process of exposing a semiconductor wafer to light via a mask is one of the processes used in preparing a semiconductor wafer with a pattern (column 1, rows 14-42). Yagi et al. disclose a multichamber apparatus comprising an exposure chamber for carrying out this process (Figure 4 and Figure 6, 606)

7. It would have been obvious to one of ordinary skill in the art at the time the Applicant's invention was made to have provided the semiconductor apparatus of Sasaki et al. as an apparatus comprising an exposure chamber for exposing a substrate with light through a mask in order to carry out a known semiconductor manufacturing step as taught by Yagi et al.

8. With respect to claim 24, said gas flow forming mechanism includes a circulation unit (24) configured to exhaust gas from said booth and to return the exhausted gas to said booth through said filter (column 5, row 64 through column 6, row 4).

9. With respect to claim 25, said gas forming mechanism includes a fan unit (20) configured to supply gas to said booth through said filter.

10. With respect to claim 26, said gas flow forming mechanism is configured to form a laminar flow of gas in said booth (column 6, rows 11-15).

11. With respect to claim 27, Sasaki et al. teach that a plurality of process chambers/units are provided and that they may be used for coating (film forming). See column 5, rows 55-56.

Response to Arguments

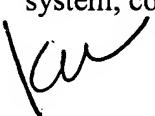
12. Applicant's arguments with respect to claims 23-27 have been considered but are moot in view of the new ground(s) of rejection. New interpretations and/or sections of the previous relied art have been used to account for Applicant's amendments.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Karla Moore whose telephone number is 571.272.1440. The examiner can normally be reached on Monday-Friday, 9:00 am-6:00 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on 571.272.1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).


Karla Moore
Patent Examiner
Art Unit 1763
3 April 2006